Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	"5194297" and copper	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 13:28
	5	"5194297" and metal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:00
L3	170417	initiator	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:00
L4	102762	3 and monomer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:01
L5	1	initiator near6 benzy	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:01
L6	1021	initiator near6 benzyl	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:01
L7	817	6 and monomer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:01
L8	375	7 and particle	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/08/11 14:01
L9	34	7 and particle near6 substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 14:01

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3670	(measur\$3 or detect\$3) near9 (particle near6 (substrate or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:31
L2	768033	1 both near2 sides	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:24
L3	277	1 and both near2 sides	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:24
L4	78	1 and (both near2 sides) near3 (substrate or wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:28
L5	6	1 and ((both near2 sides) near3 ((particle or defect) near4 (substrate or wafer)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:30
L6	5	1 and (both near2 sides) near2 (particle or defect)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:30
L7	7705	(measur\$3 or detect\$3) near9 ((particle or defect) near6 (substrate or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:31
L8	931	7 and "356"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:32
L9	25	particle near counter and 8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OʻN	2005/08/11 16:35
L10	71	particles near3 ((both near2 sides) near3 (substrate or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:36

L11	6	10 and (measur\$3 or detect\$3) near9 (particle or defect)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:37
L12	4	10 and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/11 16:37